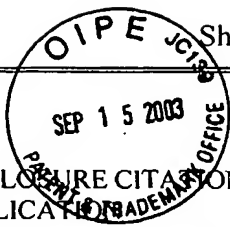


Sheet 1 of 2

FORM TPO-1449 (Modified)				Atty. Docket No. 27/217		Application No. 10/632,955		
INFORMATION DISCLOSURE CITATION IN AN APPLICATION (USE SEVERAL SHEETS IF NECESSARY)				Applicant: Nathan et al				
				Filing Date: 04 Aug 2003		Group Art Unit: 2913		
U.S. PATENT DOCUMENTS								
	EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE	
AA	<i>Jms</i>	6,580,547	Jun 03	Liu et al				
AB	<i>Jms</i>	6,444,133	Sep 02	Fajardo et al				
AC	<i>Jms</i>	6,472,804	Oct 02	Mueller et al				
AD	<i>Jms</i>	6,542,682	Apr 03	Cotteverte et al				
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION	
							YES	NO
AE								
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
AF	<i>Jms</i>	A Three Dimensional Optical Photonic Crystal, Lin et al, Journal Of Lightwave Technology Vol.17, no.11 Nov '99						
AG	<i>Jms</i>	Quasimetallic silicon micromachined photonic crystals, Temelkuran et al, Appl. Physics Letters, Vol. 78, no. 3 Jan 2001 pp 264-266						
AH	<i>Jms</i>	Fabrication of Photonic Crystals Consisting of Si Nanopillars By Plasma Etching Using Self-Formed Masks, Tada et al, pp 7253-7256, Jpn J Appl Phys, Vol 38 (1999) Pt 1, No. 12B						
AI	<i>Jms</i>	Fabrication of two-dimensional photonic crystal waveguides for 1.5um in silicon by deep anisotropic dry etching, Zijlstra et al; 1999 American Vacuum Society pp2734-2739						
AJ	<i>Jms</i>	Investigation of a channel-add/drop-filtering device using acceptor-type point defects in a two-dimensional photonic-crystal slab, Asano et al; Applied Physics Letters vol 83 No. 3 July 2003, pp407-409						
EXAMINER <i>[Signature]</i>				DATE CONSIDERED <i>7/19/05</i>				
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformation and not considered. Include copy of this form with next communication to applicant.								

Sheet 2 of 2

Form PTO-1449 (Modified)		Atty. Docket No. 27/217		Application No. 10/632,955			
INFORMATION DISCLOSURE CITATION IN AN APPLICATION FOR A PATENT (USE SEVERAL SHEETS IF NECESSARY)		Applicant: Nathan et al					
		Filing Date: 04 Aug 2003		Group Art Unit: 2813			
U.S. PATENT DOCUMENTS							
	EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
BA							
BB							
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
							YES NO
BC							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
BD	<i>JMS</i>	Electrooptical Effects in Silicon, Soref et al; JI of Quantum Electronics, vol. QE-23, no. 1 Jan 87 pp.123-129					
BE	<i>JMS</i>	Fabrication of a narrow gold wire using scanning tunneling microscopy; Okamoto et al; , Jpn J Appl Phys, Vol 36 (1997) Pt 1, No. 6B pp.3832-3833					
BF	<i>JMS</i>	Fabrication and direct transmission measurement of high-aspect-ratio two-dimensional silicon-based photonic crystal chips, Xu et al, J Opt Soc Am B/Vol 18 No. 8 August 2001pp.1084-1091					
BG	<i>JMS</i>	Defect Modes in Two-Dimensional Triangular Photonic Crystals. X. P. Feng et al , Jpn. J. Appl. Phys., 36 pp. L120-L123, 1997					
BH	<i>JMS</i>	Narrow Band Microcavity Waveguides In Photonic Crystals, Boag et al, J. Opt. Soc. Am. A, 18(11) pp. 2799-2805, 2001					
BI	<i>JMS</i>	Bipolar Semiconductor Devices; Roulston; Section 3.5.2 , Mc-Graw Hill 1990, ISBN 0-07-054120-5,					
BJ	<i>JMS</i>	Photonic Crystals: putting a new twist on light, Joannopoulos et al., Nature, vol. 386, Mar. 13, 1997, pp. 143-149					
BK	<i>JMS</i>	Design And Sensitivity Analysis Of Narrow Band Photonic Waveguides, Boag et al, URSI Radio Science Meeting, Boston, MA, July 2001, pp 33-35					
BL	<i>JMS</i>	Chapter 55 of the "Complete guide to semiconductor devices" by Kwok K. Ng, Mc-Graw Hill, 1995, ISBN 0-07-035860-5, pp 441-445					
BM	<i>JMS</i>	Chapter 15 of the "Complete guide to semiconductor devices" by Kwok K. Ng, Mc-Graw Hill, 1995, ISBN 0-07-035860-5, pp. 132-143					
EXAMINER		<i>[Signature]</i>				DATE CONSIDERED 1/14/05	
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